DERWENT-ACC-NO:

1992-067414

DERWENT-WEEK:

199951

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TITLE:

Thin-film FET for memory - has source and

drain

electrodes buried in insulation film between

upper gate

electrode and film covering lower electrode

NoAbstract

Dwg 1/9

PATENT-ASSIGNEE: CASIO COMPUTER CO LTD[CASK]

PRIORITY-DATA: 1990JP-0092021 (April 9, 1990)

PATENT-FAMILY:

LANGUAGE PUB-DATE PUB-NO

MAIN-IPC PAGES

N/ADecember 20, 1991 JP 03290970 A

005

N/A November 2, 1999 JP 2969184 B2

H01L 027/115

APPLICATION-DATA:

APPL-NO APPL-DESCRIPTOR PUB-NO

APPL-DATE

1990JP-0092021 N/A JP 03290970A

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INT-CL (IPC): H01L021/8247, H01L027/11, H01L027/115, H01L029/78

H01L029/788 , H01L029/792

ABSTRACTED-PUB-NO: JP 2969184B

EQUIVALENT-ABSTRACTS:

Optical disk having a resin substrate has a trench on the periphery when the resin substrates are adhered to each other. A groove or pit for formed on a side of a resin substrate. A 1st ceramics layer, a

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recording layer, 2nd ceramics layer and a reflection layer are laminated in order. The plates are adhered using epoxy gp. resin. A trench is formed at the periphery and a UV curing type resin is filled into the trench. The resin is cured and the periphery is cut.

ADVANTAGE - No change of mechanical characteristics at higher temp...

TITLE-TERMS: THIN FILM FET MEMORY SOURCE DRAIN ELECTRODE BURY
INSULATE FILM

UPPER GATE ELECTRODE FILM COVER LOWER ELECTRODE NOABSTRACT

DERWENT-CLASS: Ull Ul2 Ul3 Ul4

EPI-CODES: U11-C18B5; U12-B03A; U12-D02A1; U12-Q; U13-C04B2; U14-A03B7; U14-H01A;

SECONDARY-ACC-NO:
Non-CPI Secondary Accession Numbers: N1992-050492